

CLAIMS

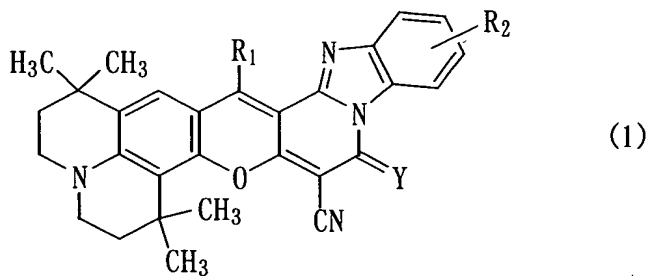
1. A negative photosensitive resin composition comprising:

- 5 (A) a photocurable resin having a photosensitive group or groups crosslinkable by light irradiation,
(B) a photoacid generator, and
(C) a photosensitizer which is a benzopyran condensed ring compound capable of increasing photosensitivity to visible
10 light with a wavelength of 480 nm or more.

2. A composition according to claim 1, wherein the proportion of the photoacid generator (B) is about 0.01 to 10 parts by weight per 100 parts by weight of the
15 resin (A).

3. A composition according to claim 1, wherein the photosensitizer (C) is a benzopyran condensed ring compound represented by Formula (1)

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wherein R_1 is hydrogen, halogen, cyano, trifluoromethyl, carboxyl or carboxylic acid ester, R_2 is hydrogen, alkyl, alkoxy, cyano, trifluoromethyl, sulfoxy or halogen, and Y is NH or O.

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4. A composition according to claim 1, wherein the proportion of the photosensitizer (C) is about 0.1 to 10 parts by weight per 100 parts by weight of the total amount of the resin (A) and photoacid generator (B).

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5. A composition according to claim 1 which further comprises, as an photoacid proliferating agent (D), an organic acid ester (a) and/or a crosslinked carbocyclic compound (b) containing a crosslinked carbocyclic skeleton which has a hydroxyl group or groups bonded to any of the crosslinked carbocyclic rings and, at a carbon atom or atoms adjacent to the hydroxyl-bearing carbon atom or atoms, a sulfonate group represented by Formula (2)

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wherein R_5 is acyl, aliphatic hydrocarbon, polycyclic aromatic hydrocarbon or a heterocyclic group.

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6. A composition according to claim 1 which is an organic solvent-based resin composition.

7. A composition according to claim 1 which is an aqueous resin composition.

8. A negative photosensitive dry film prepared
5 by applying a negative photosensitive resin composition according to claim 1 to a surface of support film, followed by drying, to form a negative photosensitive resin layer.

access limitation

10 9. A method of forming a pattern comprising the steps of:

(1) applying a negative photosensitive resin composition according to claim 1 to a substrate, followed by drying, to form a negative photosensitive resin coating,

15 (2) irradiating the resin coating with visible light directly or through a mask so as to obtain a desired pattern, and

(3) removing the unirradiated part of the negative photosensitive resin coating by development to form a
20 resist pattern coating.

10. A method of forming a pattern comprising the steps of:

(1') attaching a negative photosensitive dry film
25 according to claim 8 to a substrate so that the

photosensitive resin layer of the dry film is in contact with the substrate to form a negative photosensitive resin coating, and optionally peeling off the support film of the dry film,

- 5 (2) irradiating the resin coating with visible light directly or through a mask so as to obtain a desired pattern, and

- (3') peeling off the support film of the dry film when the support film has not been peeled off, and removing the
10 unirradiated part of the negative photosensitive resin coating by development to form a resist pattern coating.